



7/7/03  
#7/Amdt  
A

Attorney Docket No. 60188-446  
PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

RECEIVED  
JUN 27 2003  
TC 1700

In re Application of  
Masayuki ENDO, et al.

Serial No.: 10/032,542

Group Art Unit: 1756

Filed: January 02, 2002

Examiner: Daborah Chacko Davis

For: PATTERN FORMATION METHOD

AMENDMENT UNDER 37 C.F.R. § 1.111

Mail Stop Non-Fee Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the final Office Action mailed March 26, 2003, having a shortened statutory period for response set to expire on June 26, 2003, please amend the above-identified application as follows:

IN THE CLAIMS:

Please amend claim 1 as follows:

1. (Amended) A pattern formation method comprising the steps of:

forming a resist film of a chemically amplified resist material including a base polymer having a lactone group and having neither a hydroxyl group nor a carboxylic

A,